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(71) Applicant: **HONEYWELL INTERNATIONAL INC.** [US/US], Box 2245, 101 Columbia Road, Morristown, NJ 07962 (US).

(72) Inventors: **SEGAL, Vladimir**; 1906 South Sonora Drive, Veradale, WA 99037 (US). **FERRASSE, Stephane**; 15821 E. 4th, #F326, Veradale, WA 99037 (US) **ALFORD, Frank**, E 14408 16th, Veradale, Wa 99037 (US).

(74) Agents: **LATWESEN, David, G.** et al ; 601 W. First Avenue, Suite 1300, Spokane, WA 99201 (US).

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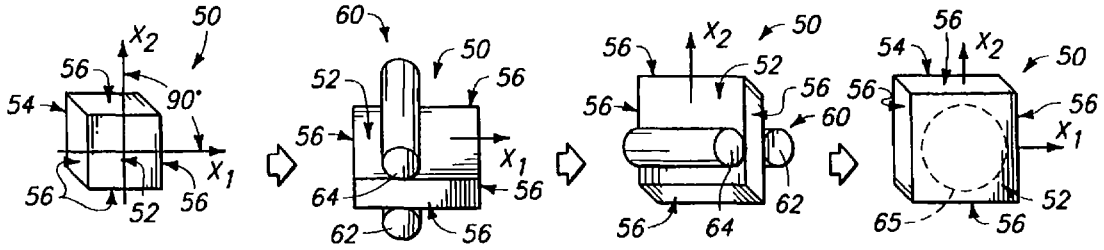
(54) Title: PHYSICAL VAPOR DEPOSITION TARGETS, AND METHODS OF FABRICATING METALLIC MATERIALS



(57) Abstract: The invention includes a physical vapor deposition target composed of a face centered cubic unit cell metal or alloy and having a uniform grain size less than 30 microns, preferably less than 1 micron; and a uniform axial or planar <220> texture. Also described is a method for making sputtering targets. The method can comprise billet preparation, equal channel angular extrusion with a prescribed route and number of passes; and cross-rolling or forging subsequent to the equal channel angular extrusion.

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